

Image  
1765



TSMC-00-151

October 6, 2003

To: Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572  
28 Davis Avenue  
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 09/867,563 05/31/01 |  
| Tsu Shih |  
A METHOD TO ELIMINATE VIA POISON  
EFFECT  
Grp. Art Unit: 1765

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56. Copies of each document is included herewith.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being  
deposited with the United States Postal Service as first class  
mail in an envelope addressed to: Commissioner for Patents,  
P.O. Box 1450, Alexandria, VA 22313-1450, on October 20, 2003.

Stephen B. Ackerman, Reg.# 37761

Signature/Date SB Ackerman 10/20/03

TSMC-00-151

Taiwan Patent Publication 383460 to Lin et al., "Dual Damascene Method," discloses a dual damascene method to cover a layer of photoresist on the dielectric and employ the mask for exposure in which the mask comprises three parts.

Taiwan Patent Publication 368732 discloses a method of fabricating a dual damascene structure to reduce the steps of photolithography and increase precision.

Sincerely,

A handwritten signature in black ink, appearing to be 'S. Ackerman', written over the printed name.

Stephen B. Ackerman,  
Reg. No. 37761

Duane (Harvard) (Cognitive)

Agitation Number

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Filing Date

05/31/00

Group Art Unit

1.765

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 OCT 22 2003  
 PATENT & TRADEMARK  
 EXAMINER  
 W. J. M.

[illegible]

## FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
					YES	NO
383460		Taiwan				
368732		Taiwan				

OTHER DOCUMENTS (Including Author, Title, Date, Portion(s) Pages, Etc.)


OXLEY

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant